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**PHOTOSENSITIVE COMPOSITION**

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**PURPOSE:** To obtain a photosensitive compsn. excellent in storage stability and having coating property by bringing a liquid photosensitive compsn. or a soln. of the resin component which constitutes the photosensitive compsn. into contact with an ion exchange resin and performing ion exchange treatment. **CONSTITUTION:** A liquid photosensitive compsn. or a soln. of the resin component which constitutes the photosensitive compsn. is brought into contact with an ion exchange resin for ion exchange treatment. The object photosensitive compsn. includes compds. generally called as a resist. As for the ion exchange resin, two kinds of resins, an anion exchange resin and a cation exchange resin, are usually used, and in this method, a cation exchange resin is mainly used to remove metal ions. The ion exchange resin is classified as a macroporous type, gel type, etc., according to kinds of base bodies, and any type of resin can be used. Further, both of a nonwater-base or a water-base resin can be used. The cation exchange resin to be used is a H<+> type as used in a conventional method.

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